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978-1-107-41104-3 - Laser and Particle-Beam Chemical Processing for Microelectronics:
Symposium held December 1-3, 1987, Boston, Massachusetts, U.S.A.

Edited by Daniel J. Ehrlich, Gregg S. Higashi and Modest M. Oprysko

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MATERIALS RESEARCH SOCIETY SYMPOSIUM PROCEEDINGS VOLUME 101

Laser and Particle-Beam Chemical Processing for Microelectronics

Symposium held December 1-3, 1987, Boston, Massachusetts, U.S.A.

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Pittsburgh, Pennsylvania

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Preface

The following is a compilation of papers presented at the Laser And Particle Beam Chemical Processing For Microelectronics Symposium of the 1987 Fall Meeting of the Materials Research Society. This symposium, held in Boston from December 1 to 3 this past year, is the sixth annual symposium held at the Fall MRS Meeting in this area of research. It began in 1982 as the symposium on Laser Diagnostics and Photochemical Processing for Semiconductor Devices and has provided a forum for the discussion of beam-enhanced surface chemical processing techniques. In the past year, there has been tremendous growth in the number of high-quality analytical studies contributed, expanding our fundamental understanding of the complex interactions involved in beam-chemical processing. In concert with these efforts, high-quality materials, surfaces, and interfaces have been prepared using beam processing techniques. The synergism displayed between the fundamental and applied research presented provides an example of the essence materials science and guarantees the continued growth of this exciting field of research.

D. J. Ehrlich
G. S. Higashi
M. M. Oprysko

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S. D. Allen
C. I. H. Ashby
D. Bauerle
I. W. Boyd
V. M. Donnelly
Y. S. Liu
J. Nishizawa

We would especially like to thank our manuscript referees for reviewing all our papers on such short notice.

Of course, we are extremely indebted to our invited speakers for highlighting the work in this field as well as for giving perspective to our endeavors:

D. E. Eastman
J. C. Polanyi
C. Wittig

D. Bauerle
I. Higashikawa
T. M. Mayer
J. Nishizawa
M. Rothschild
M. Stuke

Most importantly, however, we would like to thank all the authors for the high quality of the oral and poster presentations in the contributed paper sessions.

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